

IN THE ABSTRACT:

Please amend the Abstract of the disclosure as follows.

~~A method for measuring a dielectric constant of a thin film sample includes irradiating a sample with light at a first incident angle, whereby the light undergoes multiple internal reflections within the sample; measuring light that has transmitted through or reflected on the sample following said multiple internal reflections; and determining a complex dielectric constant of the sample based upon a spectrum of the transmitted or reflected light that has undergone said multiple internal reflections.~~

In order to measure a complex dielectric constant of a thin film on a substrate, a method includes irradiating the thin film sample with light at a first incident angle so that the light undergoes multiple internal reflections within the thin film sample. The method also includes measuring light that has transmitted through or reflected on the thin film sample following the multiple internal reflections, and determining a complex dielectric constant of the thin film sample based upon a spectrum of the transmitted or reflected light that has undergone the multiple internal reflections.